

10613378

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	Applicant(s) Abdurrahman Sezginer et al.	
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## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
RD	AA	US 2002/0135875	09/26/2002	Niu et al.	359	564	02/27/2001
RD	AB	US 2002/0158193	10/31/2002	Sezginer et al.	250	237	02/12/2002
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## FOREIGN PATENT DOCUMENTS

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							YES	NO
RD	AG	WO 02/25723 A2	03/28/2002	PCT	H01L	21/66		

## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

RD	AH	W. Yang et al., "A Novel Diffraction Based Spectroscopic Method For Overlay Metrology," SPIE's 28th Annual International Symposium and Education Program and Microlithography, February 2003, pp. 9.
RD	AI	T.A. Germer, "Measurement of lithographic overlay by light scattering ellipsometry," Proceedings of SPIE, Surface Scattering and Diffraction and Advanced Metrology II, Vol. 4780, 2002, pp. 72-79.
RD	AJ	H.T. Huang et al., "Scatterometry-Based Overlay Metrology," SPIE (Microlithography 2003), Vol. 5038, 2003. 12 pages in length.
RD	AK	M. Adel et al., "Characterization of Overlay Mark Fidelity," SPIE Meeting on MicroLithography, February 2003, 8 pages in length.

Examiner <i>[Signature]</i>	Date Considered 5/25/05
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	